

Title (en)
RADICAL GAS GENERATION SYSTEM

Title (de)
SYSTEM ZUR ERZEUGUNG VON RADIKALISCHEM GAS

Title (fr)
SYSTÈME DE GÉNÉRATION DE GAZ RADICALAIRE

Publication
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Application
EP 14898292 A 20141029

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• JP 2014078724 W 20141029
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Abstract (en)
[origin: EP3193566A1] The present invention has an object to provide, as a film formation process system of remote plasma type, a radical gas generation system in which a process can be performed evenly on, for example, a target object having a large area through the use of a radical gas. In a radical gas generation system (500) according to the present invention, a process chamber apparatus (200) includes a table (201) that causes a target object (202) to rotate. A radical gas generator (100) includes a plurality of discharge cells (70). Each of the plurality of discharge cells (70) includes an opening (102). The opening (102) is connected to the inside of the process chamber apparatus (200) and faces the target object (202). Through the opening (102), a radical gas (G2) is output. Of the plurality of discharge cells (70), a discharge cell (70) located farther from a center position of the rotation of the target object (202) in a plan view includes a larger facing surface area that is a region in which a first electrode member (1) and a second electrode member (31) face each other.

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